

REMARKS

Claim Rejections - 35 USC § 102

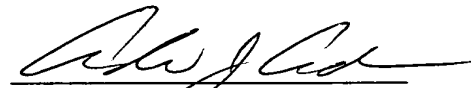
Claims 1-25 are rejected under 35 U.S.C. 102(e) as being anticipated by French (US 6,946,410). This rejection is respectfully traversed.

French discloses a method for providing nano-structures of uniform length, wherein nano-structures are coated and spatially fixed on a substrate, and then cut (e.g., by employing photolithographic patterning techniques) to a desired uniform length or distribution of lengths. In order to actually cut up the nano-structures, the patterning mask geometry must be smaller than the length of the nano-structures. The uniformly cut nano-structures may then be removed from the substrate and subsequently employed for a desired end use. The present invention, on the other hand, is directed towards a process of forming actual patterned conductors (see, e.g., page 1, line 27; page 3, line 15; page 4, line 8; page 7, line 23; etc.) by patterning a conductive layer coated on a substrate. Claim 1 has been amended to more clearly state such feature of the invention (support being found generally throughout the specification, and specifically in the drawings and above cited sections), and to more explicitly differentiate from French. French does not teach or suggest employing the patterning technique for directly obtaining patterned conductors, as opposed to uniformly cut nano-structures. The cutting of a layer of coated nano-structures in accordance with French would actually rather appear to result in very short sections of non-interconnected structures, thus decreasing electrical conductivity between individual structures, which would appear to teach away from forming actual patterned conductors. To form actual patterned conductors in accordance with the present invention, e.g., patterning masks with relatively large patterning geometry relative to the lengths of the nano-materials may be employed (as opposed to the relatively small geometries necessitated by the cutting method of French), so as not to decrease electrical conductivity between the individual nano-structures within a patterned conductor. Reconsideration of the rejection of claim 1, and all dependent claims, as anticipated by French is accordingly respectfully requested.

While claim 1 and each of the dependent claims is believed patentable over French for at least the reasons given above, it is further noted that the dependent claims additionally distinguish from French. Dependent claims 7 and 8, e.g., require that the substrate upon which the patterned conductors are formed is a substrate of a particular end-use device (i.e., either a flat-panel display or touchscreen). As French is only directed towards uniform cutting of nano-structures for subsequent use, there is no teaching or suggestion to perform the process of French directly on an end-use device substrate to form actual patterned conductors of the end-use device. Similarly, each of claims 10-12 are directed towards subsequent processing steps performed over the patterned conductors formed in the method of claim 1, which steps are useful in forming additional structure in an end-use device. As the cut nano-structures of French are removed from the substrate for subsequent end-use, these additional processing steps directly on the patterned conductive layer in accordance with the present invention are clearly not taught or suggested by French.

In view of the foregoing amendments and remarks, reconsideration of this patent application is respectfully requested. A prompt and favorable action by the Examiner is earnestly solicited. Should the Examiner believe any remaining issues may be resolved via a telephone interview, the Examiner is encouraged to contact Applicants' representative at the number below to discuss such issues.

Respectfully submitted,



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If the Examiner is unable to reach the Applicant(s) Attorney at the telephone number provided, the Examiner is requested to communicate with Eastman Kodak Company Patent Operations at (585) 477-4656.